

Interference Search

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3	(gate adj (oxide or insulation or dielectric) and gate adj electrode and spacer and ion adj implant\$5 and trench and oxide adj (layer or liner or film) and barrier and contact adj hole).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 13:43
L2	5	(oxide adj (layer or liner or film) near7 except near2 spacer).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 13:45
L3	1	(form\$5 near4 oxide adj (layer or liner or film) near7 except near2 spacer).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 13:45
L4	0	(form\$5 near4 oxide adj (layer or liner or film) same except near2 spacer).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 13:45
L5	0	("forming an oxide layer on substrate").clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/13 14:42